

ABSTRACT OF THE DISCLOSURE

This invention relates to a processing apparatus for processing a sample such as a substrate. The apparatus includes a process chamber having an exposure apparatus for transferring a pattern onto a substrate as a sample in a predetermined atmosphere, a load-lock chamber connected to the process chamber, a transfer mechanism for transferring the substrate between the load-lock chamber and a coater/developer, a clean booth which covers the transfer path of the transfer mechanism, and a transfer atmosphere forming mechanism for flowing a clean gas in the clean booth.